

	Application No.	Applicant(s)
Notice of Allowability	10/604,627	JANG, WEN-YUEH
	Examiner	Art Unit
	Ida M. Soward	2822
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in 5) or other appropriate comm RIGHTS. This application is a	n this application. If not included unication will be mailed in due course. THIS
1. This communication is responsive to the Applicant's amen	ndment filed February 22, 20	<u>05</u> .
2. ☑ The allowed claim(s) is/are <u>1,2,4,5,7-9 and 19-26</u> .		
3. X The drawings filed on 29 June 2004 are accepted by the	Examiner.	
 Acknowledgment is made of a claim for foreign priority to a) All b)	ve been received. ve been received in Application ocuments have been receive " of this communication to file	on No d in this national stage application from the
 A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give CORRECTED DRAWINGS (as "replacement sheets") must be subr including changes required by the Notice of Draftsper 	ves reason(s) why the oath o ust be submitted. rson's Patent Drawing Revie	r declaration is deficient.
1) hereto or 2) to Paper No./Mail Date (b) nicluding changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	r's Amendment / Comment o	he drawings in the front (not the back) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview S Paper No. /08), 7. ☐ Examiner's	uformal Patent Application (PTO-152) ummary (PTO-413), /Mail Date Amendment/Comment Statement of Reasons for Allowance
		AMIR ZAPARIAN

DETAILED ACTION

This Office Action is in response to the Applicant's amendment filed February 22, 2005.

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a correspondence with Belinda Lee on March 2, 2005.

The application has been amended as follows:

- 1. claim 18 filed August 6, 2003 has been cancelled; and
- 2. claims 18-25 filed February 22, 2005 have been renumbered and amended as follows:

Claims 10- 1718 (cancelled)

1819. (currently amended) A resistance random access memory structure, comprising:

- a plurality of word lines in a substrate:
- a plurality of reset lines coupled to said word lines;
- a dielectric layer on said substrate;

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a plurality of memory units in said dielectric layer, each said memory including a bottom electrode, a top electrode, and a resistive thin film between said top electrode and said bottom electrode, said bottom electrodes of said memory units in a same column being coupled to one of said reset lines;

a plurality of said bit lines on said memory units, said top electrodes of said memory units in a same row being coupled to one of said bit lines; and

a plurality of reset line contact windows in said dielectric layer, each of said reset line contact windows being coupled to one of said reset lines(.).

1920. (currently amended) The resistance random access memory structure of claim 1819, wherein said reset lines are set in said word lines, the ion type of said reset lines being opposite to the ion type of said word lines.

2021. (currently amended) The resistance random access memory structure of claim 1819, wherein said reset lines are set on the surface of said word lines, and wherein the material of said reset lines is comprised of a metal.

2122. (currently amended) The resistance random access memory structure of claim 1819, further comprising a plurality of word line contact windows in said dielectric layer, wherein each of said word line contact windows are coupled to one of said word lines.

2223. (currently amended) The resistance random access memory structure of claim 2122, further comprising a plurality of doped regions in said word lines, wherein each of said doped regions are coupled to one of said word line contact

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windows, and wherein an ion types of said doped regions and said word lines is are the

same.

2324. (currently amended) The resistance random access memory structure

of claim 1819, wherein said memory units in a same column are set on a surface of said

reset lines.

2425. (currently amended) The resistance random access memory structure

of claim <u>819</u>, wherein said resistive thin film material is resistance-reversible.

2526. (currently amended) The resistance random access memory structure

of claim 1819 wherein said resistive thin film material is selected from colossal magneto

resistive thin films and oxidation thin films having Perovskite structure.

Allowable Subject Matter

Claims 1-2, 4-5, 7-9 and 19-26 are allowed.

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

The following patents are cited to further show the state of the art with respect to resistance random access memory structures:

Gogl et al. (US 2002/0039308 A1)

Hikawa et al. (5,753,553)

Hoffmann et al. (US 2002/0018361 A1)

Hsu et al. (US 6,753,562 B1)

Ooishi et al. (US 2002/0110016 A1)

Ooishi (US 2002/0181272 A1)

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Park et al. (US 6,815,784 B2)

Sakata et al. (US 6,573,586 B2).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ida M. Soward whose telephone number is 571-272-1845. The examiner can normally be reached on Monday - Thursday 6:30am to 5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

IMS March 2, 2005

AMIK ZAKABIAN SUPPRVICCRY PATENT EXAMINER ARCHNOLOGY CENTET 282 :